



MacPherson Kwok Chen & Heid LLP

2001 Gateway Place, Suite 195E

San Jose, CA 95110

Tel. (408) 392-9250

Fax (408) 392-9262

2402 Michelson Drive, Suite 210

Irvine, CA 92612

Tel. (949) 752-7040

Fax (949) 752-7049

Email: mailbox@macpherson-kwok.com

April 2, 2003

BOX AF
Commissioner For Patents
Washington, D.C. 20231

Re: Applicant(s): Woo Sik Yoo
Assignee: WaferMasters, Inc.
Title: Method for H2 Recycling In Semiconductor Processing System
Serial No.: 09/828,518
Examiner: Olivia T. Luk
Docket No.: M-8608US
Filed: April 6, 2001
Group Art Unit: 2812

Dear Sir:

Transmitted herewith are the following documents in the above-identified application:

- (1) Return Receipt Postcard;
- (2) This Transmittal Letter (in duplicate);
- (3) Response to Final Office Action (8 pages).

- ☒ No additional fee is required.
☐ The fee has been calculated as shown below:

CLAIMS AS AMENDED

	Claims Remaining After Amendment		Highest No. Previously Paid For		Present Extra	Rate	Additional Fee
Total Claims	14	Minus	20	=	0	x \$18.00	\$ 0
Independent Claims	3	Minus	3	=	0	x \$84.00	\$ 0
<input type="checkbox"/> Fee for Request for Extension of Time							\$
Total additional fee for this Amendment:							\$
<input checked="" type="checkbox"/> Conditional Petition for Extension of Time: If an extension of time is required for timely filing of the enclosed document(s) after all papers filed with this transmittal have been considered, an extension of time is hereby requested.							
<input type="checkbox"/> Please charge our Deposit Account No. 50-2257 in the amount of							\$
<input checked="" type="checkbox"/> Also, charge any additional fees required and credit any overpayment to our Deposit Account No. 50-2257							
Total:							\$ 0

Express Mail Label No.:

EV 252 518 710US

Respectfully submitted,

Theodore P. Lopez
Attorney for Applicants
Reg. No. 44,881

RECEIVED
APR - 7 2003
TC 2800 MAIL ROOM

AF
2800



AMENDMENT UNDER 37 CFR 1.116
EXPEDITED PROCEDURE-
EXAMINING GROUP 2812

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Yoo, Woo Sik
Assignee: WaferMasters, Inc.
Title: Method for H₂ Recycling in a Semiconductor Processing System
Serial No.: 09/828,518 Filing Date: April 6, 2001
Examiner: Luk, Olivia T. Group Art Unit: 2812
Docket No.: M-8608 US

#4/B
Bm
J. McMillan
4/10/03
Jal
5/9/03

Irvine, California
April 2, 2003

BOX AF
COMMISSIONER FOR PATENTS
Washington, D. C. 20231

RECEIVED
APR - 7 2003
TC 2800 MAIL ROOM

RESPONSE TO FINAL OFFICE ACTION

Dear Sir:

In response to the Final Office Action dated February 3, 2003, Applicants submit the following amendments and remarks.

IN THE CLAIMS

The following is a clean version of the entire set of pending claims. In accordance with 37 C.F.R. §1.121(c)(1)(ii), Attachment A provides a marked-up version of the claims containing the newly introduced changes. Please amend Claims 1, 2-7, 16, 23 as follows.

1. (Twice Amended) A process for recycling a vapor-phase chemical comprising:
- introducing vapor-phase chemicals taken from the group consisting of NH₃, N₂O, SiF₄, SiH₄, TiCl₄, N₂, Ar, HCl, and SiCl₄ and including pure H₂ gas into a reactor with sufficient supplied energy to cause a first reaction in said reactor;
- exhausting gases from said reactor resulting from said first reaction;

B1
cont